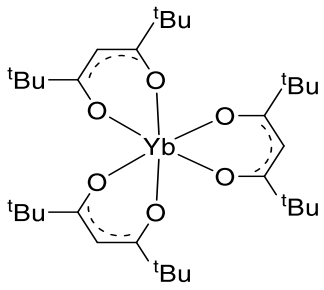
Catalog # 70-0100 Tris(2,2,6,6-tetramethyl-3,5-heptanedionato)ytterbium(III), 99% (99.9%-Yb) (REO)
[Yb(TMHD)3]



Thermal Behavior:

- Melting point: 166-169°C [1]; 165-167°C [2]; 163°C [3]
- Vapor pressure measurements in ref [4]

Technical Notes:

1. ALD/CVD precursor for deposition and dopant of Yb thin films.

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Yb_2O_3	ALD	170°C	-	O_3	250-400°C	5
$YbMn_xO_y$	ALD	123°C	1.5-2 Torr	$Mn(thd)_3$, O_3	275°C	6
$LnYb_xTi_yO_z$	ALD	-	-	$Ln(thd)_3$, O_3 $TiCl_4$, H_2O	300°C	7
$Yb:YVO_4$	ALD	128°C	-	$Y(thd)_3$, $V(thd)_2$, O_3	260°C	8
$(Yb,Er)_2O_3$	ALD	130°C	1.5-3 Torr	$Er(thd)_3$	300°C	9
$Al_2O_3:Yb$	ALD	195°C	-	Me_3Al, O_3	350°C	10

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